## Amendments to the Claims

This listing of claims will replace all prior versions, and listings of claims in the application.

## **Listing of Claims:**

1-14. (cancelled).

15. (currently amended) A chemical vapor deposition apparatus comprising:

a load-lock chamber;

a processing chamber mounted on said load-lock chamber;

an air purge line <u>adapted to supply and exhaust gas</u> connected with said load-lock chamber, wherein said air purge line supplies the load-lock chamber with air including H<sub>2</sub>O gas; and,

a vacuum pump connected to the air purge line and adapted to exhaust the residual gases from the load-lock chamber.

16. (previously presented) The apparatus as recited in claim 15, further comprising:

a vent line connected to the load-lock chamber and adapted to provide an inert gas to the load-lock chamber.

- 17. (previously presented) The apparatus as recited in claim 16, wherein said vent line is connected to said vacuum pump.
- 18. (previously presented) The apparatus as recited in claim 17, further comprising an  $O_2$  gas line connected to said air purge line.
- 19. (previously presented) The apparatus as recited in claim 18, further comprising a filter connected to said air purge line.
  - 20. (cancelled)
- 21. (original) The apparatus as recited in claim 18, wherein the  $O_2$  gas line is connected to the vacuum pump.
- 22. (original) The apparatus as recited in claim 18, further comprising mass flow controllers connected to the air purge line, the vent line and the  $O_2$  gas line so as to regulate flows and amounts of the air including  $H_2O$ , the inert gas and  $O_2$  gas, respectively.